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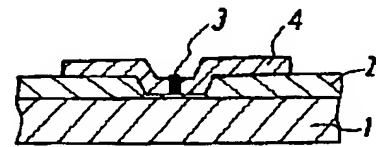
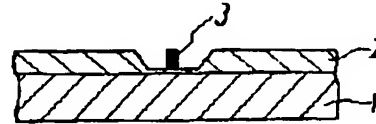
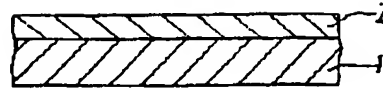
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TITLE : MANUFACTURING METHOD FOR THIN
FILM MAGNETIC HEAD



ABSTRACT : PURPOSE: To simplify a gap forming process, and to prevent a gap from peeling and inclining by using a part of sliding protection film as a gap member, and forming a magnetic gap integrally with the sliding protection film.

CONSTITUTION: On an element substrate 1, a sliding protection film 2 is formed by sputtering and the like. Next, etching is done by using a resist as a mask, the gap is formed by the same materials with the sliding protection film on the sliding protection film 2. At that time, without etching the sliding protection film to the element substrates, several hundreds and thousands μ m is left, and a gap 3 and the sliding protection film 2 are connected integrally. Next, a bottom magnetic core 4 is formed by plating. After that, an upper magnetic core, a loading conductor and so on are formed, and after connecting a support substrate, the element substrate is dissolved. And after exposing the sliding protection film surface, the surface is dry-etched or ground lightly, and the gap is exposed. Since the exposed sliding protection film surface is ground or dry-etched, and the magnetic gap is exposed, it becomes unnecessary to newly form a gap film to form the gap, and the film forming process can be eliminated.

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